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## Ellipsometric investigation of $\text{ZnFe}_2\text{O}_4$ thin films in relation to magnetic properties

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We report an influence of disorder on structural and magnetic properties of  $\text{ZnFe}_2\text{O}_4$  thin films grown at temperatures ranging from 400 °C to 600 °C by pulsed laser deposition in  $\text{O}_2$  atmosphere on  $\text{SrTiO}_3$  (100) substrates evidenced by properties of electronic transitions observed in the dielectric function. Inversion of the normal spinel structure was found to be one of the main mechanisms responsible for the increase in the magnetic response for the lowest growth temperature. The enhanced feature in the dielectric function located at  $\sim 3.5$  eV, related to the transition involving tetrahedrally coordinated  $\text{Fe}^{3+}$  cations, corresponds to the dominating magnetic coupling between the octahedral and tetrahedral lattice sites, responsible for the overall ferrimagnetic behaviour of the film grown at the lowest temperature. © 2016 AIP Publishing LLC. [<http://dx.doi.org/10.1063/1.4944898>]

Spinel oxides are being extensively investigated and continue to receive a great amount of interest due to their wide range of possible high-frequency and high-power applications, including microwave, magnetic and magneto-optical recording devices, sensors, and electronic information mass storage.<sup>1–3</sup>  $\text{ZnFe}_2\text{O}_4$  (ZFO) with a normal spinel ion distribution formula  $[\text{Zn}_A^{2+}][\text{Fe}_B^{3+}]_2\text{O}_4^{2-}$ , where A and B subscripts denote tetrahedral and octahedral lattice sites, respectively, is antiferromagnetic with a Néel temperature of about 10 K.<sup>2</sup> Depending on the deposition parameters and method, tunable electronic and magnetic properties are possible and are closely related to crystallographic properties.<sup>1,4–7</sup> However, the mechanism responsible for the observed ferrimagnetic behaviour at room temperature is still not fully understood, and two different arguments can be found, namely, spinel inversion<sup>8</sup> and defect induced magnetism due to cation and oxygen vacancies.<sup>9</sup> Both theories support the A-O-B interaction dominating over the B-O-B interaction resulting in the observed ferrimagnetic behaviour. Spectroscopic ellipsometry has been shown to be a useful technique to probe the electronic structure of the materials based on the optical transitions.<sup>10–12</sup> In this paper, we present a relation between the magnetic properties of ZFO and its electronic structure studied by spectroscopic ellipsometry and provide an explanation for the observed behavior which could shed light on the controversy in literature.

ZFO thin films were deposited on  $\text{SrTiO}_3$  (100) substrates by pulsed laser deposition (PLD). A KrF excimer laser source ( $\lambda = 248$  nm and pulse duration  $\sim 20$  ns) was used to ablate the ZFO target, energy density of the laser beam on the target was kept around  $2 \text{ J cm}^{-2}$  with a repetition rate of 15 Hz. Films were grown at different temperatures, ranging from 400 °C to 600 °C and under oxygen partial pressure of  $p_{\text{O}_2} = 0.016$  mbar. The pressure used was chosen in order to minimize and obtain similar concentration of oxygen vacancies for all the samples as determined from previous oxygen partial pressure dependent study for this

material.<sup>2</sup> The crystalline structure of the samples was analysed by X-ray diffraction (XRD)  $2\Theta - \omega$  scans using a wide-angle Phillips X'Pert Bragg-Brentano diffractometer with  $\text{Cu K}_\alpha$  radiation. Magnetic properties were measured in a MPMS-7 superconducting quantum interference device (SQUID) from Quantum Design. The dielectric function,  $\tilde{\epsilon} = \epsilon_1 + i\epsilon_2$ , of the thin films was determined by means of spectroscopic ellipsometry in a wide spectral range from 0.5 eV to 8.5 eV at room temperature and angles of incidence of 60° and 70°. <sup>13</sup> A commercial rotating analyzer spectroscopic ellipsometer, *J. A. Woollam Co. Inc.* VUV-VASE, in polarizer-compensator-sample-analyser (PCSA) configuration was used for this purpose. The ellipsometry spectra were analyzed by means of transfer matrix technique for a layer stack model containing a semi-infinite layer for the substrate, a layer for the spinel material, and a surface roughness layer, composed of a Bruggeman effective medium approximation mixture of the dielectric function of the thin film with 50% void, each described by its thickness and optical constants. Approximation calculation procedure is similar to the one presented in Ref. 10.

XRD  $2\Theta - \omega$  scans for the investigated thin films are shown in Fig. 1. Along with the substrate peak, in the measured range, the (400)- and (800)-reflections corresponding to the spinel structure were observed with no additional observable secondary phases, which reveals highly oriented growth of deposited films. However, a shift in the film peak towards higher angle (Fig. 1(b)) confirms a reduction of the lattice parameter with increase in growth temperature. For 600 °C, it is closest to the bulk value of 8.44 Å.<sup>1,14–17</sup> The lattice constants of thin films, calculated by the Scherrer equation and extrapolated from  $\cos^2(\Theta)$ , are listed in Table I. Also, with increasing substrate temperature, an increase in peak intensity is apparent, stating an improvement of the crystallinity. These modifications in the lattice parameter and the crystallinity are possibly due to the variations in the cation disorder and/or oxygen vacancies and, therefore, there is a lattice relaxation towards normal spinel structure for highest deposition temperatures, considering similar surface roughness as

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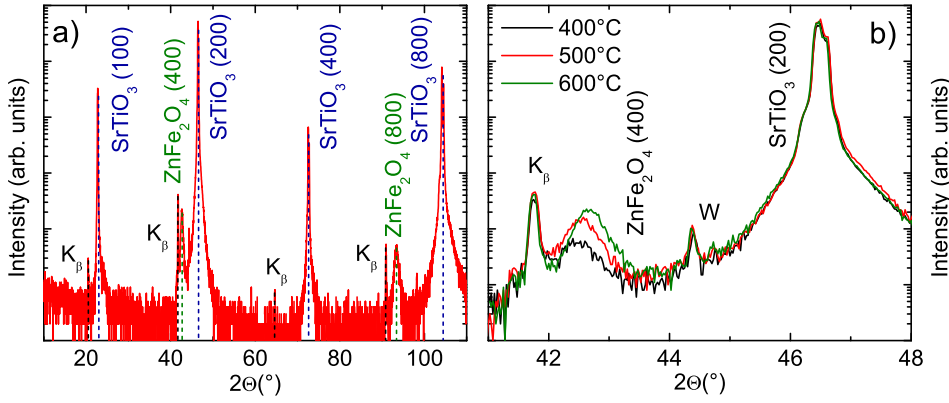


FIG. 1. XRD  $2\theta - \omega$  scans for ZFO thin film grown at  $600^\circ\text{C}$  (a) and for the ZFO thin films for different growth temperatures (b). Substrate reflexes marked by  $K_\beta$  and W correspond to Cu  $K_\beta$  and W  $L_\alpha$  spectral lines of the X-ray tube, respectively.

TABLE I. Calculated lattice parameter, thickness of the film and surface roughness, magnetization saturation  $M_{Sat}$  and magnetization remanence  $M_{Rem}$  measured at 5 K, transition energies for Gaussian (G) and critical point model (CPM0) along with the amplitude for  $G_2$  as well as the amplitude ratio,  $G_2/(G_1 + G_3)$ , listed for each growth temperature. The error estimated for the specified values is in the range of the last digit. The boldface numbers correspond to magnetization values and values obtained from the model dielectric function used in Figure 2(c).

Growth temperature ( $^\circ\text{C}$ )	Lattice constant ( $\text{\AA}$ )	Film thickness (nm)	Surface roughness (nm)	$M_{Sat}$ (emu/g)	$M_{Rem}$ (emu/g)	$G_1$ (eV)	CPM0 (eV)	$G_2$ (eV)	$G_2$ Amp ([1])	$G_3$ (eV)	Amp Ratio	$G_4$ (eV)	$G_5$ (eV)	$G_6$ (eV)
400	8.54	40.3	1.6	<b>60.89</b>	<b>35.98</b>	2.72	2.89	3.38	<b>1.25</b>	3.81	0.68	5.36	5.84	6.84
500	8.51	41.7	1.3	<b>27.80</b>	<b>15.73</b>	2.51	2.72	3.49	<b>0.44</b>	3.98	0.46	5.27	5.71	6.19
600	8.49	41.0	1.4	<b>21.66</b>	<b>11.49</b>	2.50	2.72	3.54	<b>0.29</b>	3.98	0.30	5.27	5.70	6.33

well as the thickness of the samples, Table I.<sup>5</sup> Changes are more evident for the increase in growth temperature from  $400^\circ\text{C}$  to  $500^\circ\text{C}$ , being smaller for further increase up to  $600^\circ\text{C}$ . The film deposited at a substrate temperature of  $300^\circ\text{C}$  was found to be X-ray amorphous.

Magnetization of thin films as a function of the applied magnetic field is shown for 5 K and 300 K in Fig. 2. Here, data are presented after subtracting the diamagnetic contribution from the substrate. It is visible from the B-H curves that all the samples exhibit ferrimagnetic order. Magnetization

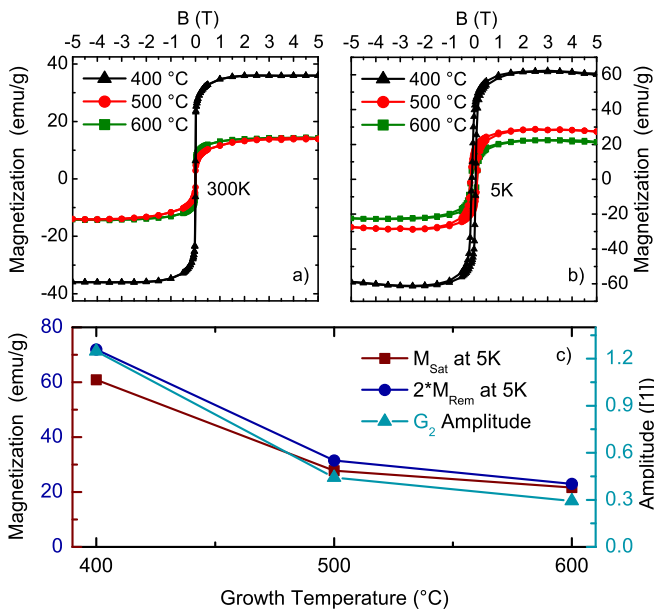


FIG. 2. Magnetization as a function of applied magnetic field at room temperature (a) and at 5 K (b) with deposition temperature indicated. Saturation and twice of remanence magnetization measured at 5 K as well as the amplitude of the transition involving tetragonally coordinated  $\text{Fe}^{3+}$  ions obtained from the model dielectric function versus growth temperature (c).

has been found to be reduced with increase in the deposition temperature (see Table I). It is in coincidence with the variation in the crystallinity and the lattice parameter observed in XRD, i.e., the variation is significant between the samples prepared at  $400^\circ\text{C}$  and  $500^\circ\text{C}$ , while a small decrease in magnetization with further increase in growth temperature ( $600^\circ\text{C}$ ) is visible only for measurements at 5 K (Fig. 2(b)).

To understand this variation of magnetization with the deposition temperature, we determined the dielectric function of all samples using spectroscopic ellipsometry. For an optically isotropic sample, the measured ellipsometric quantities  $\Psi$  and  $\Delta$  are defined by the ratio  $\rho = r_p/r_s = \tan \Psi \exp(i\Delta)$  of the complex reflection coefficients of p- and s-polarized light,  $r_p$  and  $r_s$ , respectively. The ratio is related to the real and imaginary parts of complex reflectivity. The experimental data were modelled by means of parametric model dielectric function (MDF), developed for the entire spectral range for the films as well as for the substrate, consisting of a series of 7 contributing functions, namely, M0-critical point model functions (CPM0) and Gaussian oscillators.<sup>18</sup> Regression analysis was applied to best match the parametric MDF to the numerically inverted MDF. Based on the resonance energies, transitions were assigned from previous studies of the optical as well as magneto-optical properties of this material.<sup>10-12</sup> The absorption coefficient as well as the Kramers-Kronig consistent optical constants, calculated from the parametric MDF approximation, along with the individual contributions to the model are shown in Figs. 3 and 4, respectively. Transition energies for each oscillator and relevant amplitudes are listed in Table I, (see supplementary material for further details<sup>19</sup>).

Fig. 3 shows the deduced absorption coefficient for the three thin films. A clear difference of the absorption bands is visible for the three films with the main features located at  $\sim 3.9\text{ eV}$  and  $\sim 6.1\text{ eV}$ . Low absorption below  $\sim 2\text{ eV}$

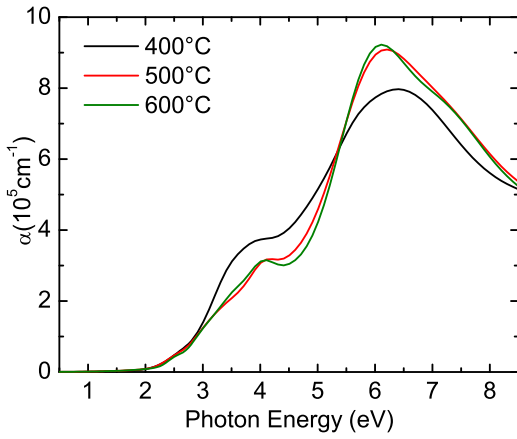


FIG. 3. Absorption coefficient  $\alpha$  derived from numerical inversion for ZFO deposited at temperatures indicated.

demonstrates low concentration of  $\text{Fe}^{3+}$ - $\text{Fe}^{2+}$  exchange in our insulating ZFO thin films in contrast to materials such as  $\text{Fe}_3\text{O}_4$  and conducting ZFO having a strong absorption in that spectral range.<sup>5,10–12</sup> Features visible in the MDF, Fig. 4 (top panel), mainly correspond to transitions between the  $\text{O}_{2p}$  band and bands of  $\text{Fe}^{3+}$  and  $\text{Zn}^{2+}$  cations. While features below  $\sim 4.5$  eV,  $G_1$ ,  $G_2$ ,  $G_3$ , correspond to transitions involving 3d bands of  $\text{Fe}^{3+}$  cations, above this energy,  $G_4$ ,  $G_5$ , and  $G_6$ , correspond to transitions from  $\text{O}_{2p}$  band to 4s as well as higher lying bands of  $\text{Fe}^{3+}$  cation and from  $\text{O}_{2p}$  band to 4s band of  $\text{Zn}^{2+}$  cation, respectively.

As observed in Fig. 4 (inset), there is a redshift of the band placed at  $G_1$  as well as a blueshift for the band at  $G_3$  which is more evident from 400 °C to 500 °C. These bands arise from crystal field split states with  $\Delta_{Oh}$  ( $=10Dq$ ) of  $\sim 1.09$  eV and  $\sim 1.48$  eV for samples grown at 400 °C and 600 °C, respectively. With the latter value being closest to the bulk data and experimental values, corresponding to least amount of distortion,<sup>20,21</sup>  $\Delta_{Oh}$  suggests a crystal field splitting between the two different bands and is related to transitions from the  $\text{O}_{2p}$  band to  $t_{2g}$  and  $e_g$  bands of the octahedral  $\text{Fe}_{3d}$  cations.

The transition located at  $G_2$  hints to the presence of  $\text{Fe}^{3+}$  on tetrahedral lattice sites and serves as evidence for

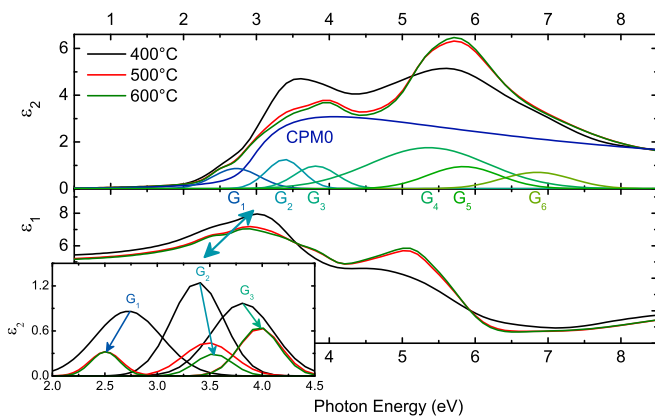


FIG. 4. Real part (bottom) and imaginary part (top) of the Kramers-Kronig consistent optical constants calculated from the parametric model for ZFO thin films grown at indicated temperatures. Color coded individual contributions to the parametric model for  $\epsilon_2$  are shown for the sample deposited at the lowest temperature. The inset shows change in amplitude of three oscillators,  $G_1$ ,  $G_2$ , and  $G_3$ , with respect to the deposition temperature.

disorder within the crystal structure. Prior studies have shown the highest magneto-optical response of this peak for ZFO thin films grown at low temperature and thus relate this feature to a transition either from  $\text{O}_{2p}$  to tetrahedrally coordinated  $\text{Fe}^{3+}$  cation or to an inter-sublattice (A-B) charge transfer transition.<sup>10,12,22,23</sup> This peak becomes more pronounced as the normal spinel becomes more inverted and is the highest for  $\text{Fe}_3\text{O}_4$  and  $\text{Li}_{0.5}\text{Fe}_{2.5}\text{O}_4$  inverse spinel materials.<sup>22–25</sup> The increase in oscillator amplitude of this transition with decreasing growth temperature is directly related to the increase in saturation magnetization as well as the remanence magnetization measured at 5 K (Fig. 2(c) and Table I).

Since the increase of the oscillator amplitude of  $G_2$  is greater than the amplitude increase of  $G_1$  and  $G_3$  with decreasing deposition temperature, see inset of Fig. 4 and amplitude ratio in Table I, two phenomena are possible. Firstly, a possible inversion mechanism where  $\text{Zn}^{2+}$  moves to the octahedral site and  $\text{Fe}^{3+}$  moves to the tetrahedral site, with decreasing growth temperature, thus following Eq. (1), where  $x$  is the inversion coefficient corresponding to the degree of cation disorder

$$[\text{Zn}_{1-x}^{2+}\text{Fe}_x^{3+}]_A[\text{Zn}_x^{2+}\text{Fe}_{2-x}^{3+}]_B\text{O}_4^{2-}. \quad (1)$$

On the other hand, presence of  $\text{Fe}^{3+}$  cations on nominally unoccupied tetrahedral sites is also possible and has been investigated in previous works.<sup>8,26,27</sup> Nonetheless, the presence of  $\text{Fe}^{3+}$  cations on tetrahedral sites leads to the ferrimagnetic pair coupling to be dominant over the antiferromagnetic pair coupling, resulting in the increase of ferrimagnetic magneto-static behaviour.

In summary, we have shown a variation of the magneto-static properties of ferrite thin films as a function of the growth temperature. The changes have been related to the changes in the octahedral and tetrahedral site occupancy as suggested by spectroscopic ellipsometry. Namely, the presence of  $\text{Fe}^{3+}$  cations located on tetrahedrally coordinated lattice sites serves as a reasonable explanation for the observed increase in magnetization saturation and remanence with decreasing growth temperature.

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